

# CMS-HPK-Campaign: IV/CV-characteristics of the first sample of irradiated diodes

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a: Karlsruhe Institute of Technology

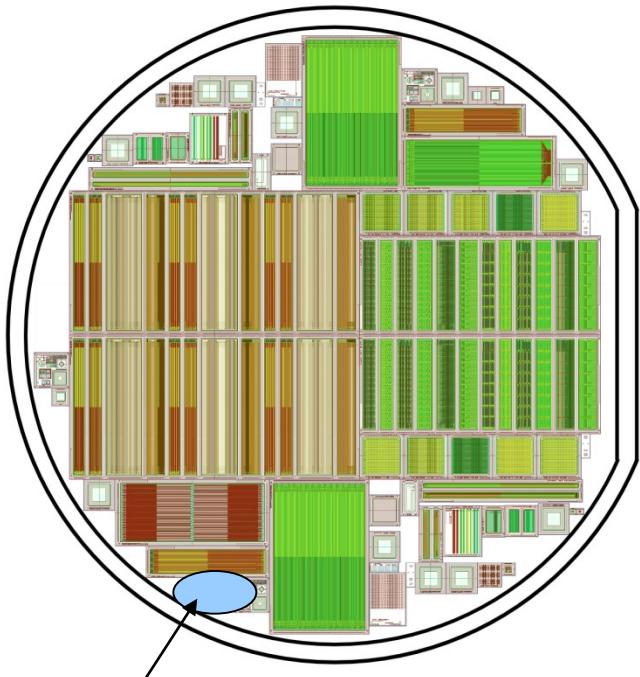
b: University of Hamburg

c: Deutsches Elektronen SYnchrotron

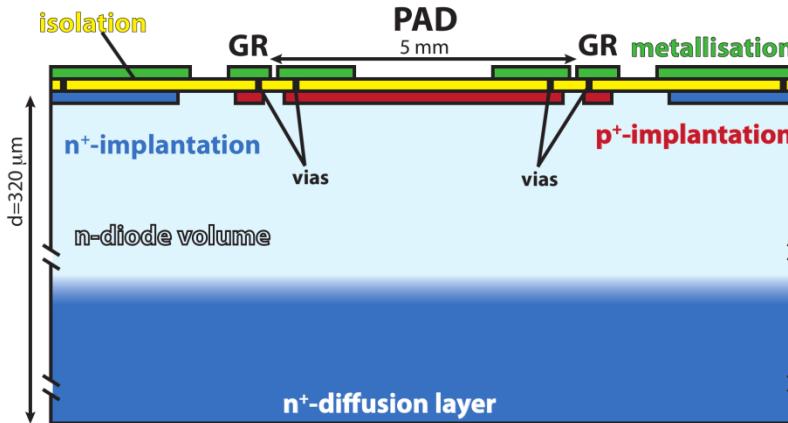
# Overview

- Introduction to material and irradiation
- Characteristics of the unirradiated diodes
- Results of irradiated diodes current-voltage measurements
- Results of irradiated diodes capacitance-voltage measurements

# Material Overview



Used Diodes  
 (L\_05:  $A=0.25 \text{ cm}^2$   
 S\_15:  $A=0.044 \text{ cm}^2$ )



Active thickness:  
 120  $\mu\text{m}$ , 200  $\mu\text{m}$ , 320  $\mu\text{m}$

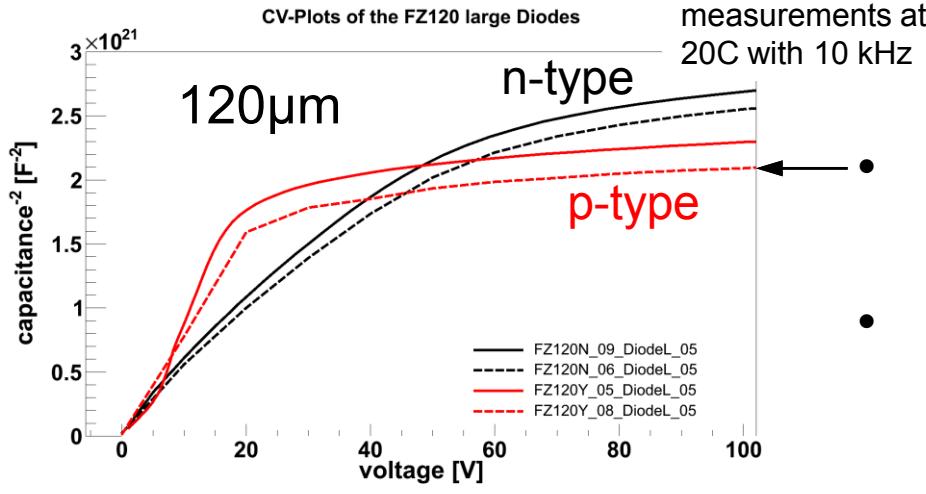
Alexandra Junkes

wafer	n-Typ	p-Typ (p-spray)
FZ 320 $\mu\text{m}$	X	X
FZ 200 $\mu\text{m}$	X	X
FZ 120 $\mu\text{m}$	X	X

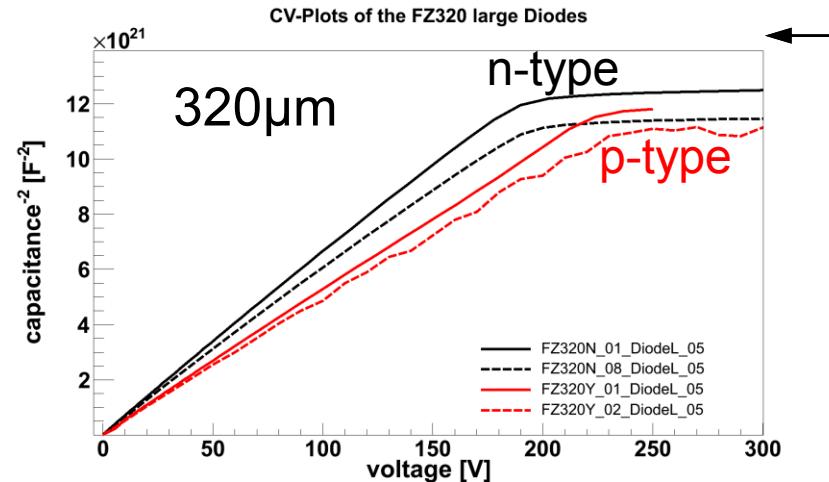
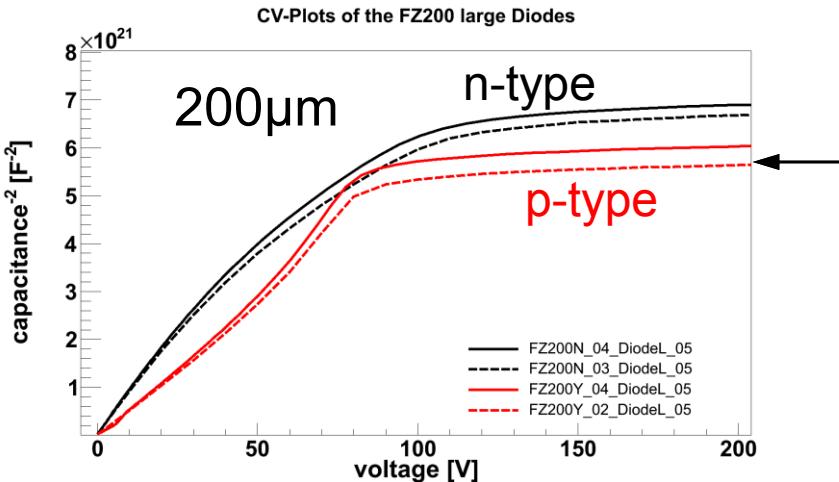
# Irradiation Overview

- This first irradiation a special step to check if the deep-diffusion material works, before starting the whole campaign
- p-type and n-type Floatzone material of three thicknesses: 120 $\mu$ m, 200 $\mu$ m and 320 $\mu$ m
- One large and one small Diode per type and irradiation-set
- Three irradiation sets, with a fluence of 10<sup>14</sup> neq:
  - neutron (reactor, 10<sup>14</sup> neq)
  - proton (25 MeV, 1.09\*10<sup>14</sup> neq)
  - mixed (neutron (reactor, 10<sup>14</sup> neq) + proton (25 MeV, 1.09\*10<sup>14</sup> neq))

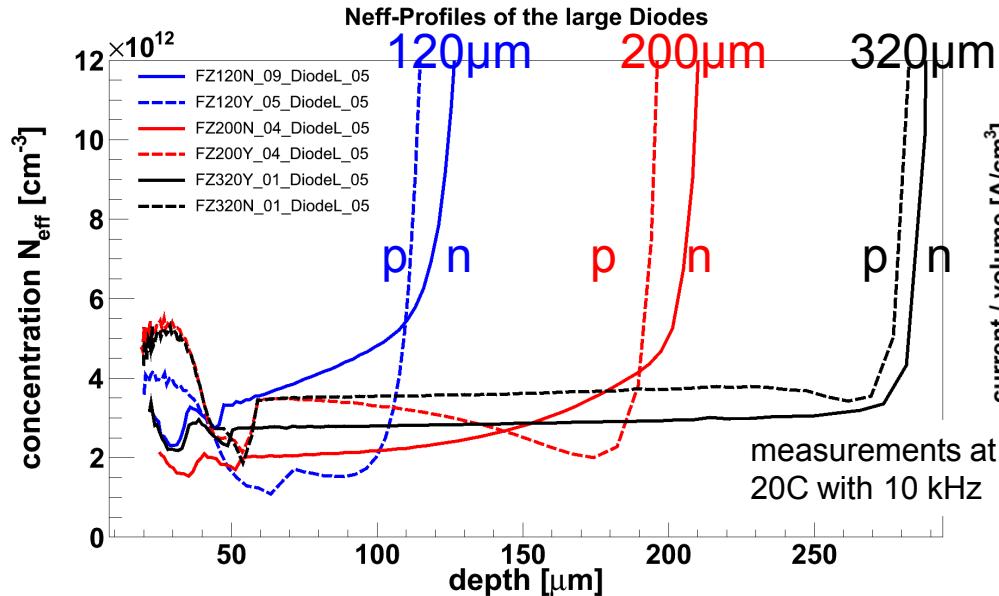
# Characteristics of the unirradiated Diodes



- n-type has generally lower capacitance than p-type
- 120 $\mu$ m and 200 $\mu$ m have very different shapes (see Talk of Alexandra Junkes)



## Characteristics of the unirradiated Diodes II

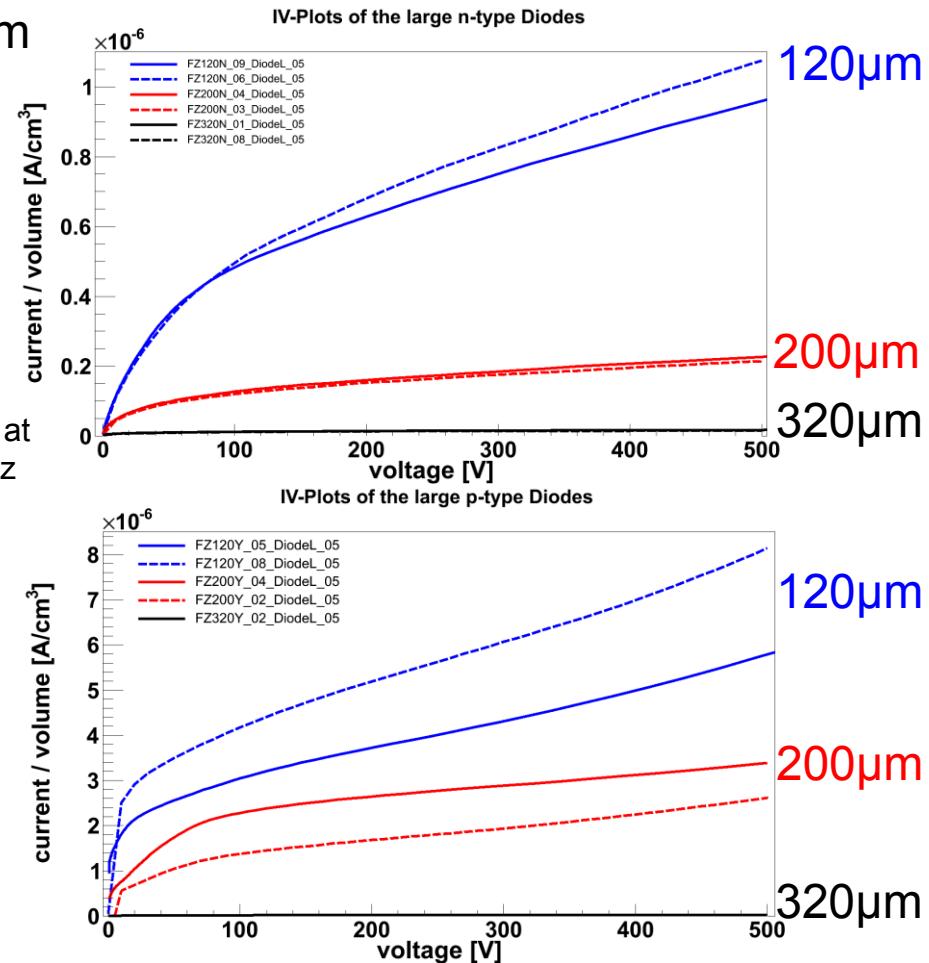


**Neff-Profile:**

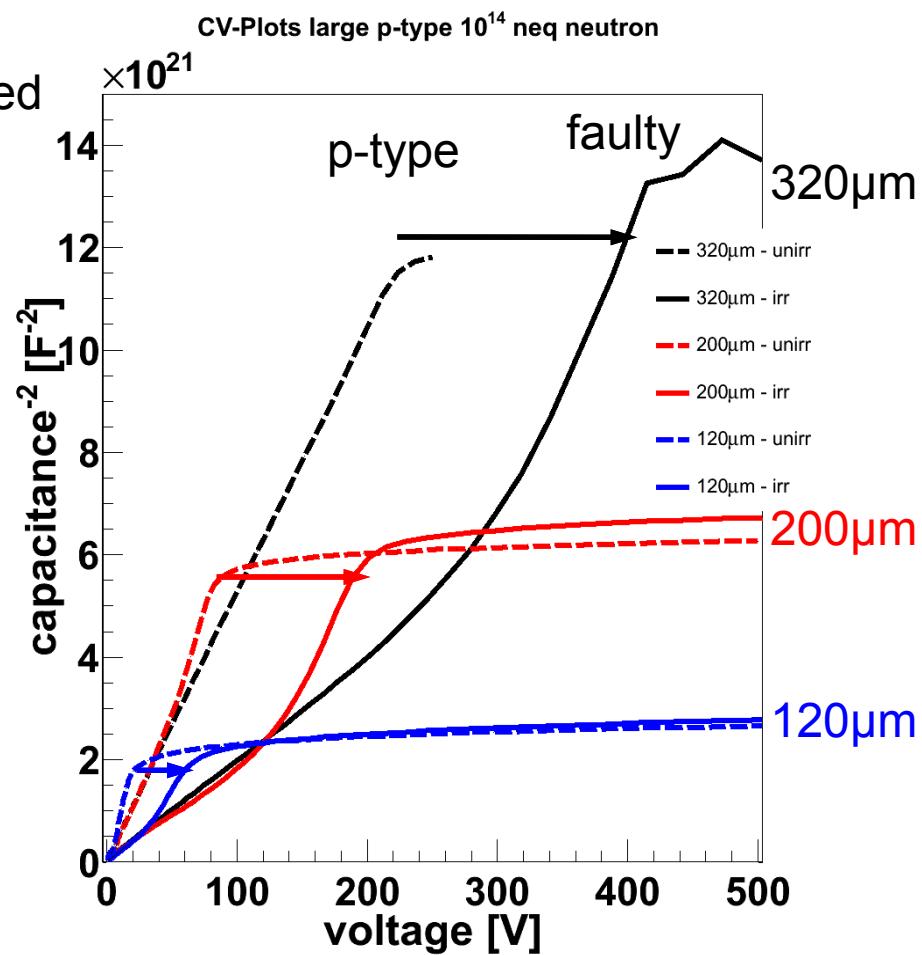
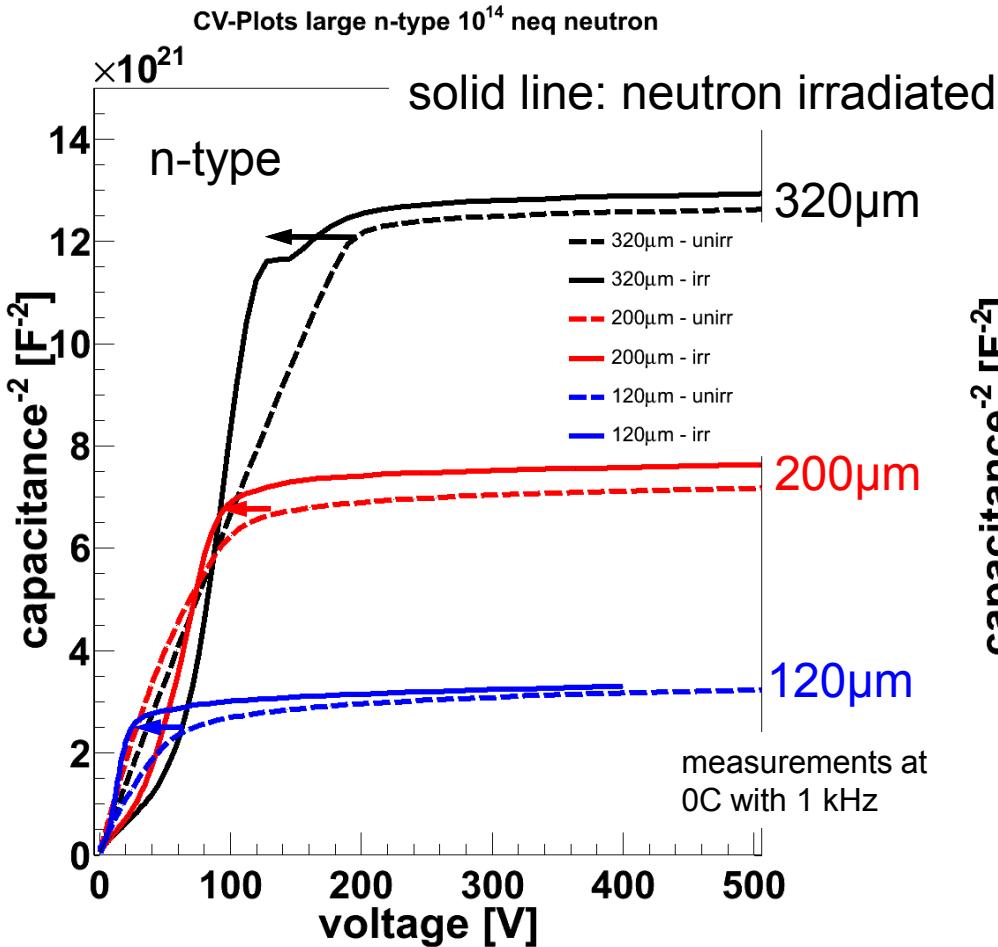
- Very different active thicknesses
- N-type: Neff increases with depth
- P-type: Neff decreases over volume

**IV-Plots:**

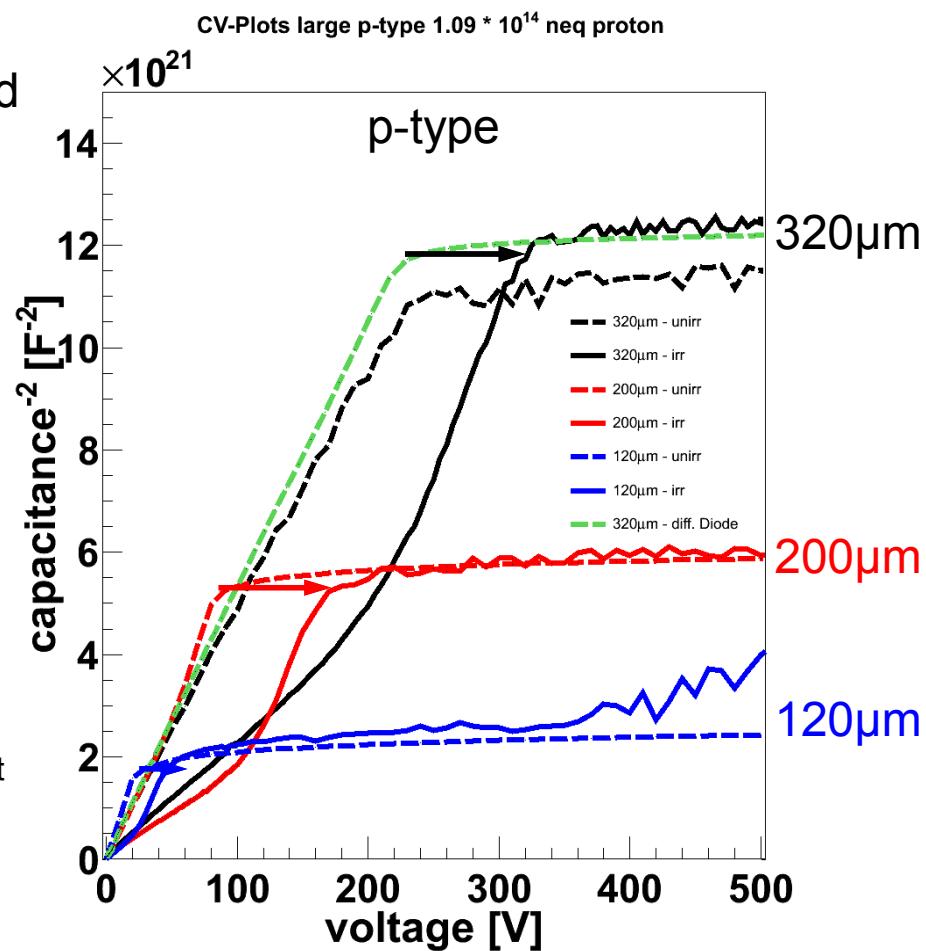
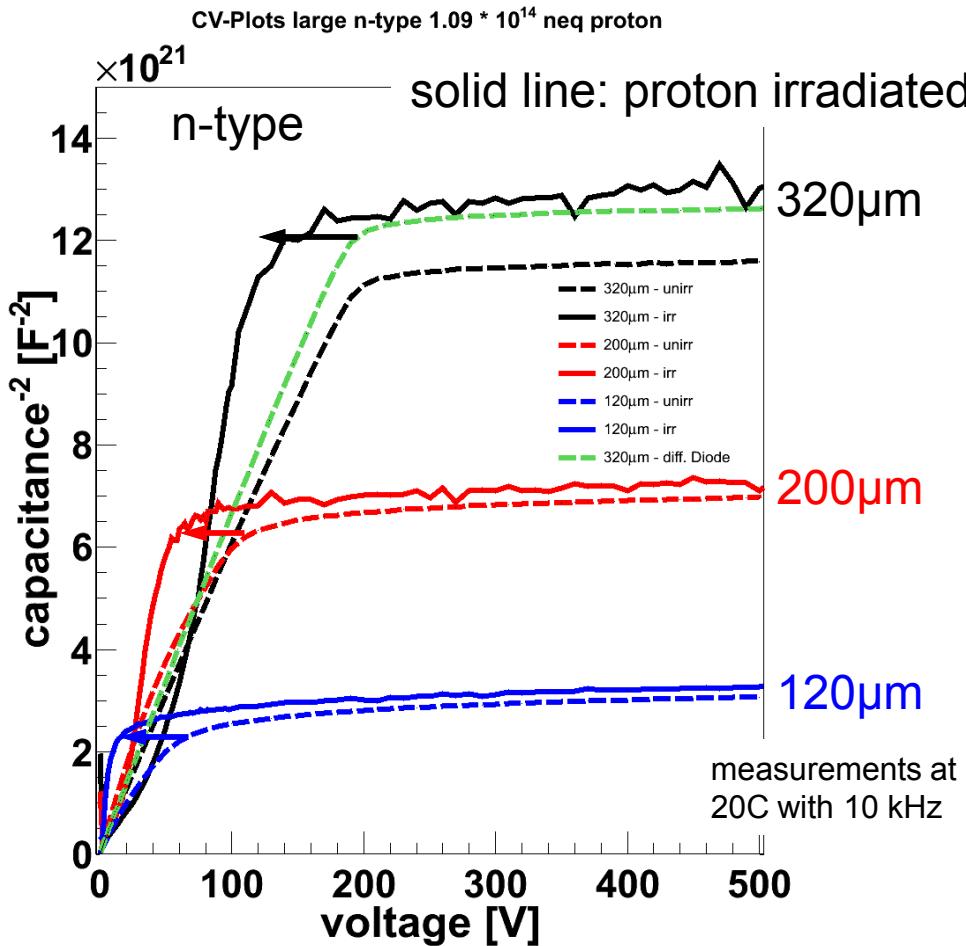
- Current decreases with thickness
- Spread in material from different wafers



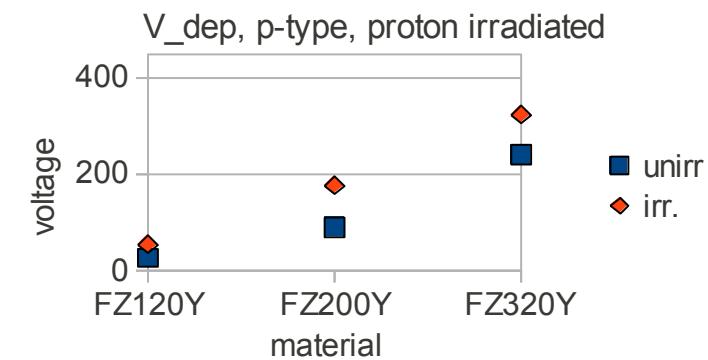
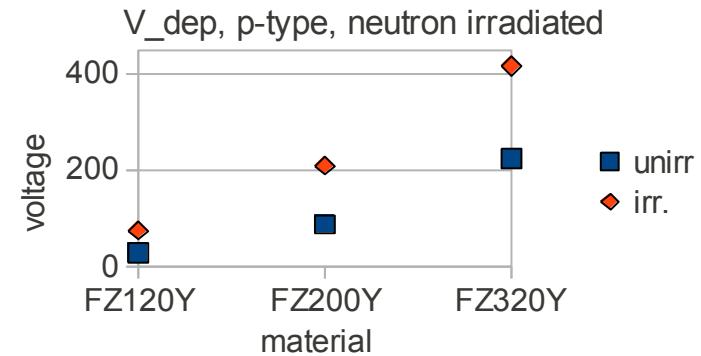
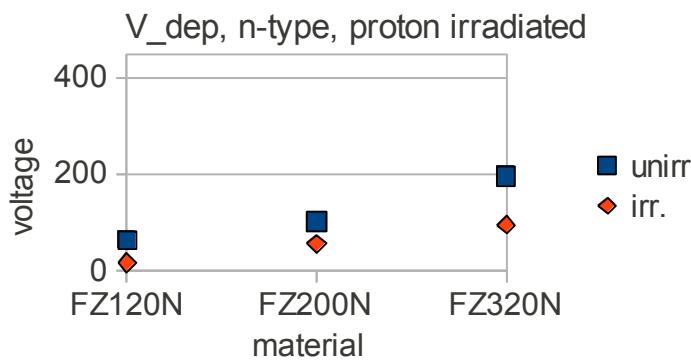
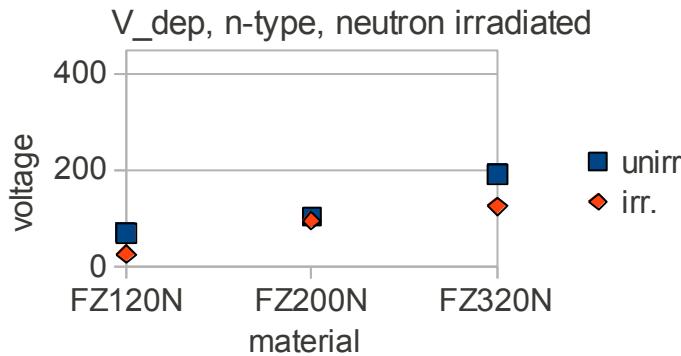
# Neutron irradiated - CV



## Proton irradiated - CV



## CV - summary

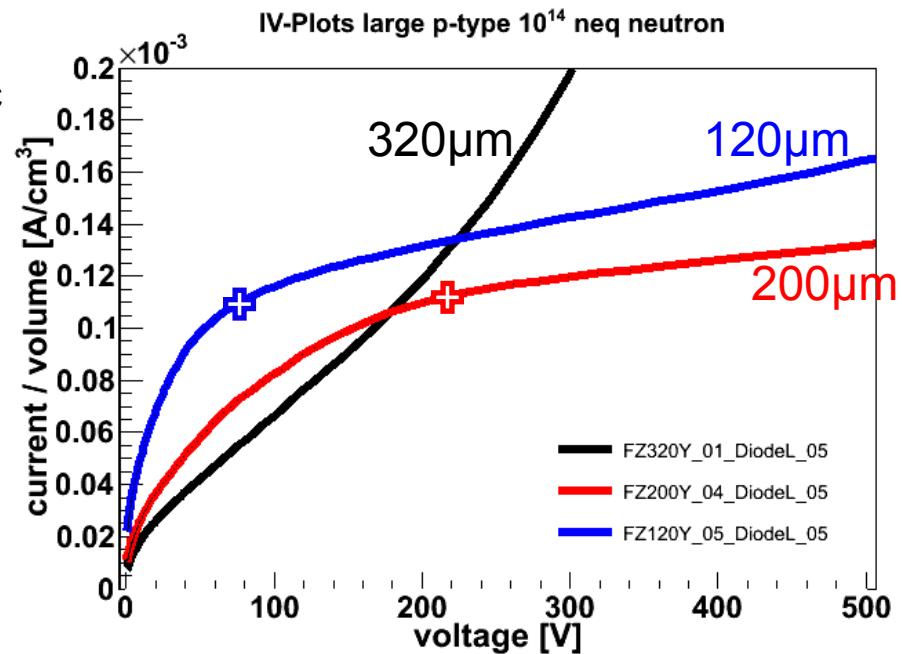
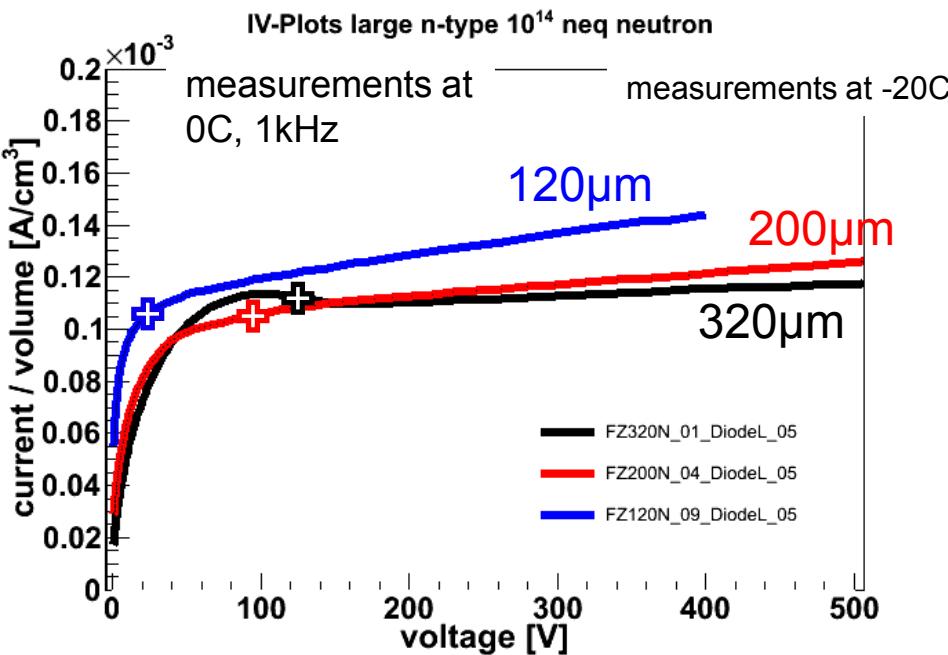


N-type: decreasing depletion voltage

P-type: increasing depletion voltage

No difference between proton and neutron irradiation

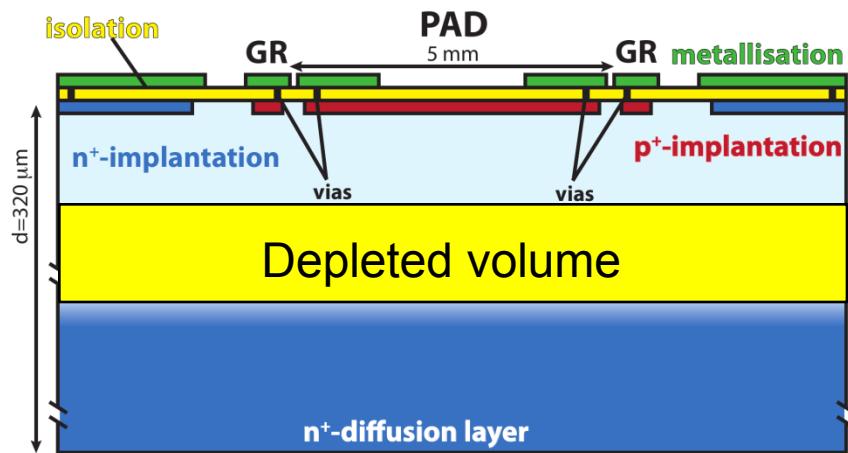
## Neutron irradiated - IV



Small bump in the front for  $320\mu\text{m}$   
 → a hint for type-inversion

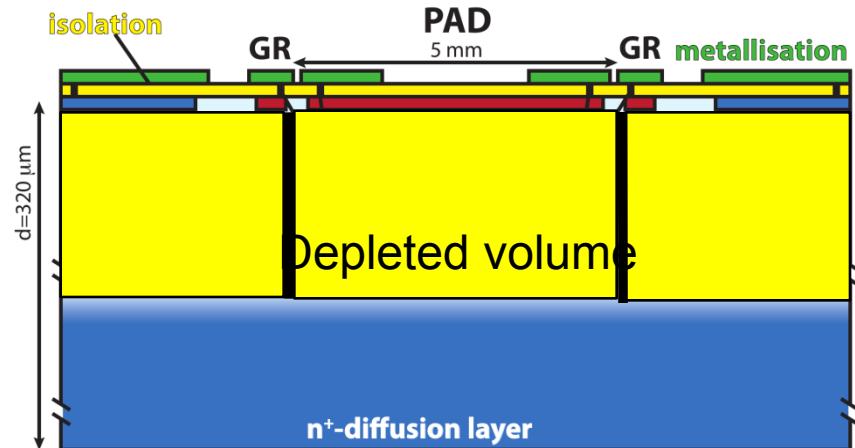
- Volume-currents are all in same range
- Slope of current above depletion is stronger for thinner diodes

# Depletion after type-inversion

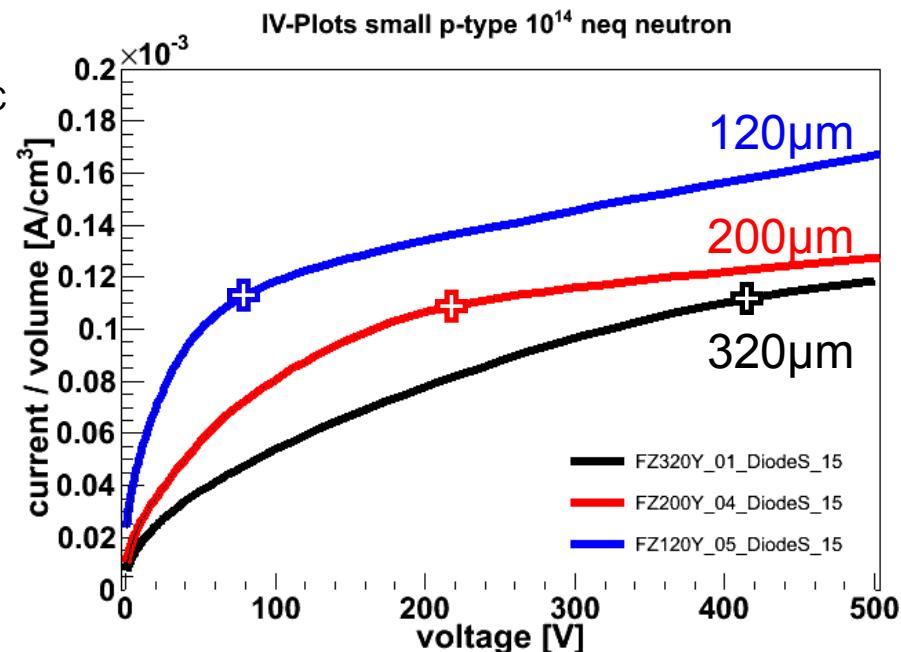
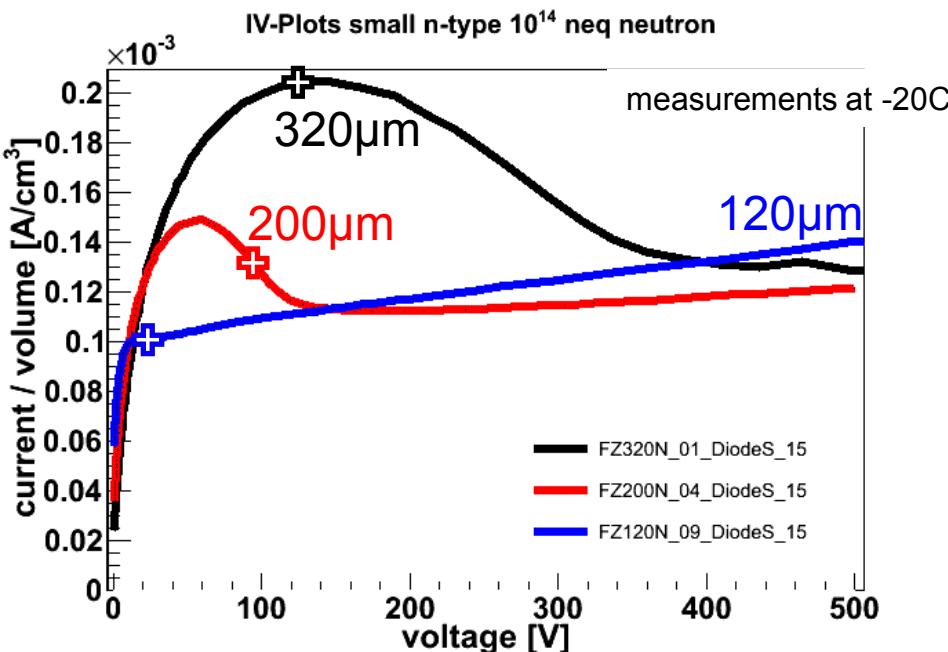


Overdepletion after type-inversion  
 Guard-ring collects outer current

Underdepletion after type-inversion



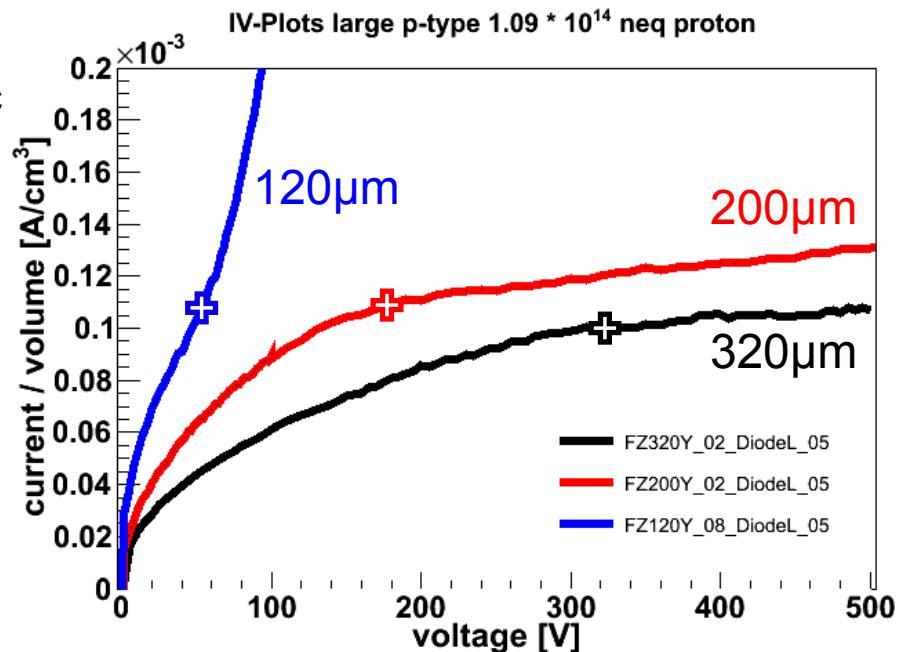
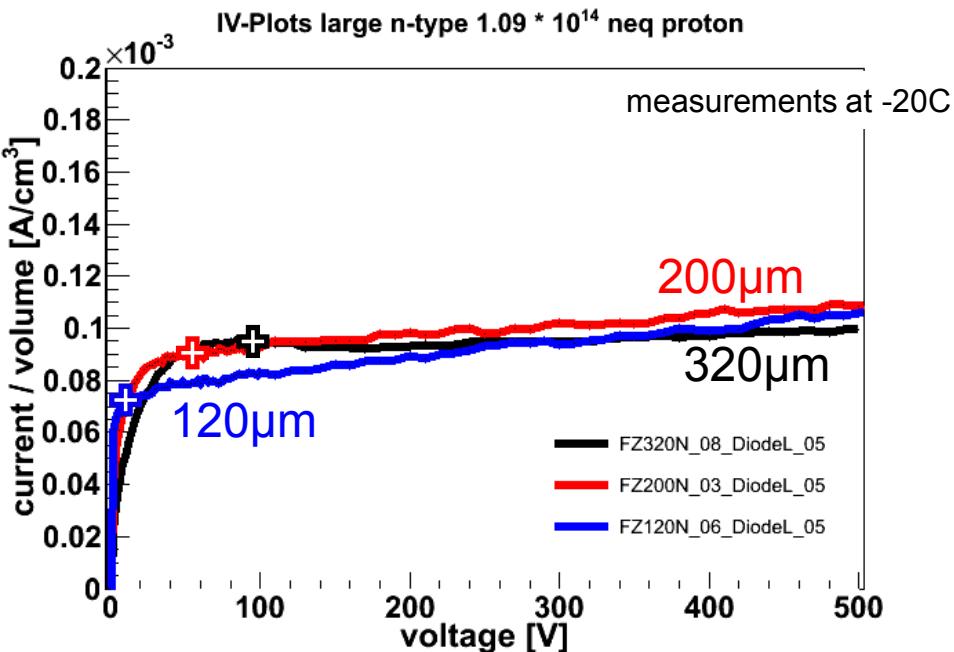
## Neutron irradiated – small Diodes - IV



Bumps in the front of all 3 diodes

- Volume-currents are all in same range
- Slope of current above depletion is stronger for thinner diodes

## Proton irradiated - IV

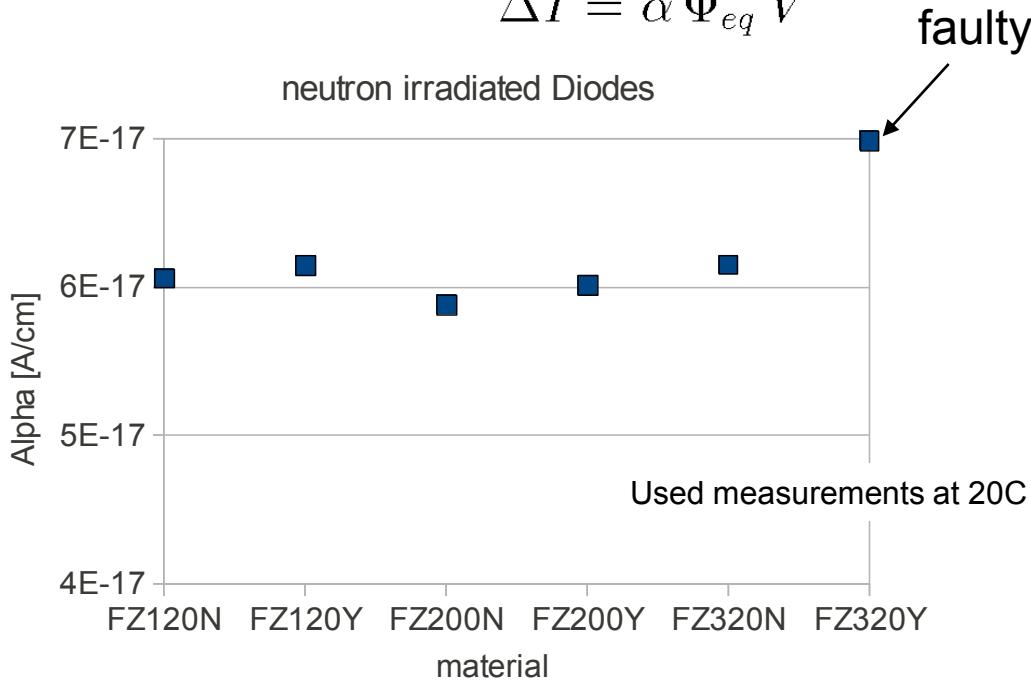


- Volume-currents are all in same range
- Slope of current above depletion is stronger for thinner diodes

# Alpha

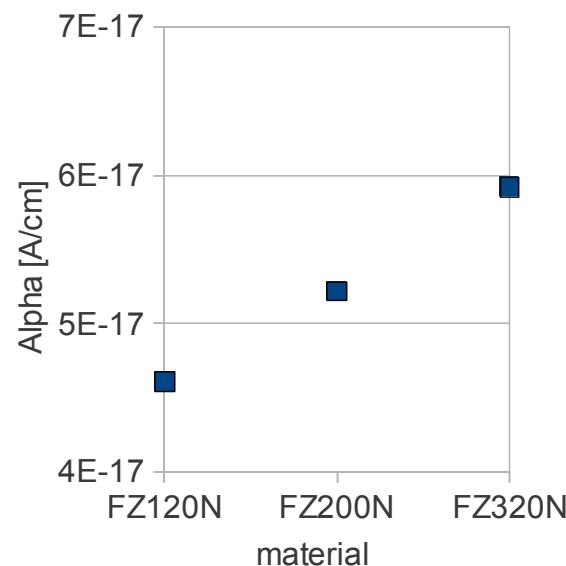
$$\Delta I = \alpha \Phi_{eq} V$$

neutron irradiated Diodes



Careful, no annealing done!  
 (but nevertheless in the right order)

proton irradiated Diodes



Short annealing done (10min@60C,  
 approx. 5.2 E-17 expected)

## Conclusions and Outlook

- All n-type materials show a decrease of the depletion-voltage (and signs of type-inversion)
- All p-type materials show an increase of the depletion-voltage
- IV- and CV-curves still have the slope due to deep-diffusion
- Volume-normalization is difficult (volume changes with voltage)

Still a lot of structures wait for treatment → big irradiation campaign to be started

**The deep-diffusion doesn't look like a show-stopper!**